

**RECEIVED**

FEB 27 2003

TC 1700

PATENT

AF/1765 \$

#8  
1A  
3/3/03**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

<b>Applicant:</b> Branz, Howard M.	<b>Examiner:</b> Umez Eronini, Lynette T.
<b>Serial No.:</b> 09/714,331	<b>Art Unit:</b> 1765
<b>Filed:</b> November 16, 2000	
<b>For:</b> METHOD FOR IMPROVING THE STABILITY OF AMORPHOUS SILICON	<b>Docket No.:</b> NREL-99-10

Assistant Commissioner for Patents  
Box Non-Fee Amendment  
Washington, D.C. 20231

I CERTIFY THAT, ON FEBRUARY 20, 2003, THIS PAPER IS BEING  
DEPOSITED WITH THE U.S. POSTAL SERVICE AS FIRST CLASS MAIL IN  
AN ENVELOPE ADDRESSED TO THE COMMISSIONER FOR PATENTS,  
WASHINGTON, D.C. 20231.

*Brenda E. Brantley*  
Brenda E. Brantley

**RESPONSE UNDER 37 C.F.R. § 1.116**

This response is to the Final Office Action mailed November 20, 2002. No fee is believed to be necessary. However, should any fee be required for entry of this paper, the Commissioner is authorized to charge our Deposit Account 14-0460 and is requested to notify us of the same.

**REMARKS**

Claims 1-18 are currently pending. The following remarks are fully responsive to the Office Action identified above, and Applicant respectfully requests reconsideration of the present rejections.

**Claim Rejections – 35 USC § 103**

Claims 1-3 and 8-17 were rejected under 35 U.S.C. 103(a) as being unpatentable over Hollingsworth (U.S. Pat. No. 5,759,745) in view of Fukaya et al. (U.S. Pat. No. 4,581,009). Specifically, the Office Action stated that Hollingsworth reports a method of forming a hydrogenated amorphous silicon layer in which a thin photoresist layer of